

# Supporting Information

## Single-Step Direct Growth of Graphene on Cu Ink towards Flexible Hybrid Electronic Applications by Plasma-Enhanced Chemical Vapor Deposition

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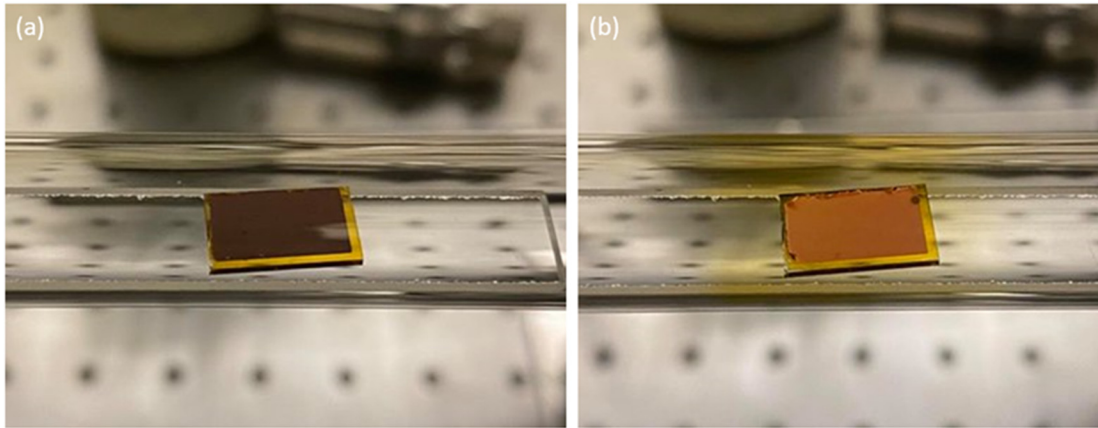


Figure S1: Images of the Cu ink sample (a) before PECVD and (b) after PECVD.

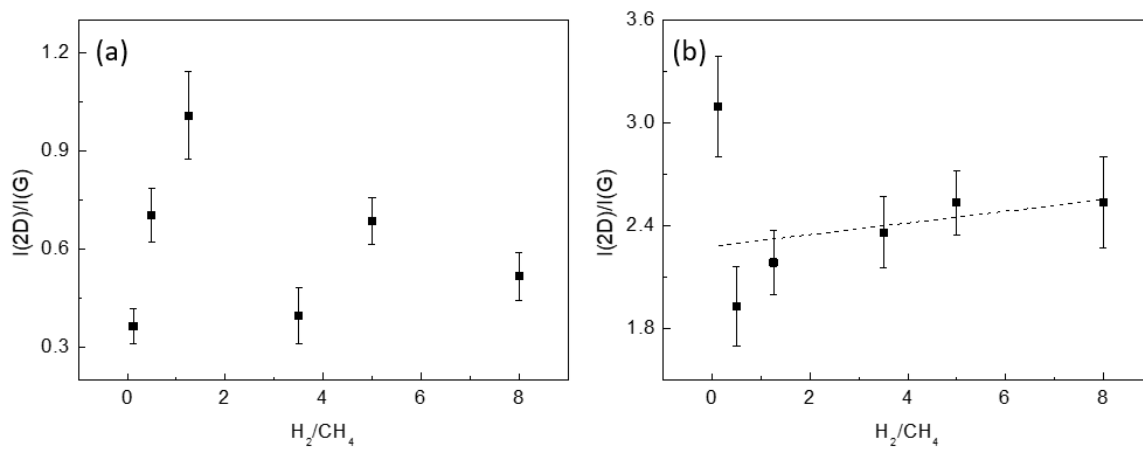


Figure S2.  $I(2D)/I(G)$  vs  $H_2/CH_4$  at (a) 500 mtorr and (b) 750 mtorr.

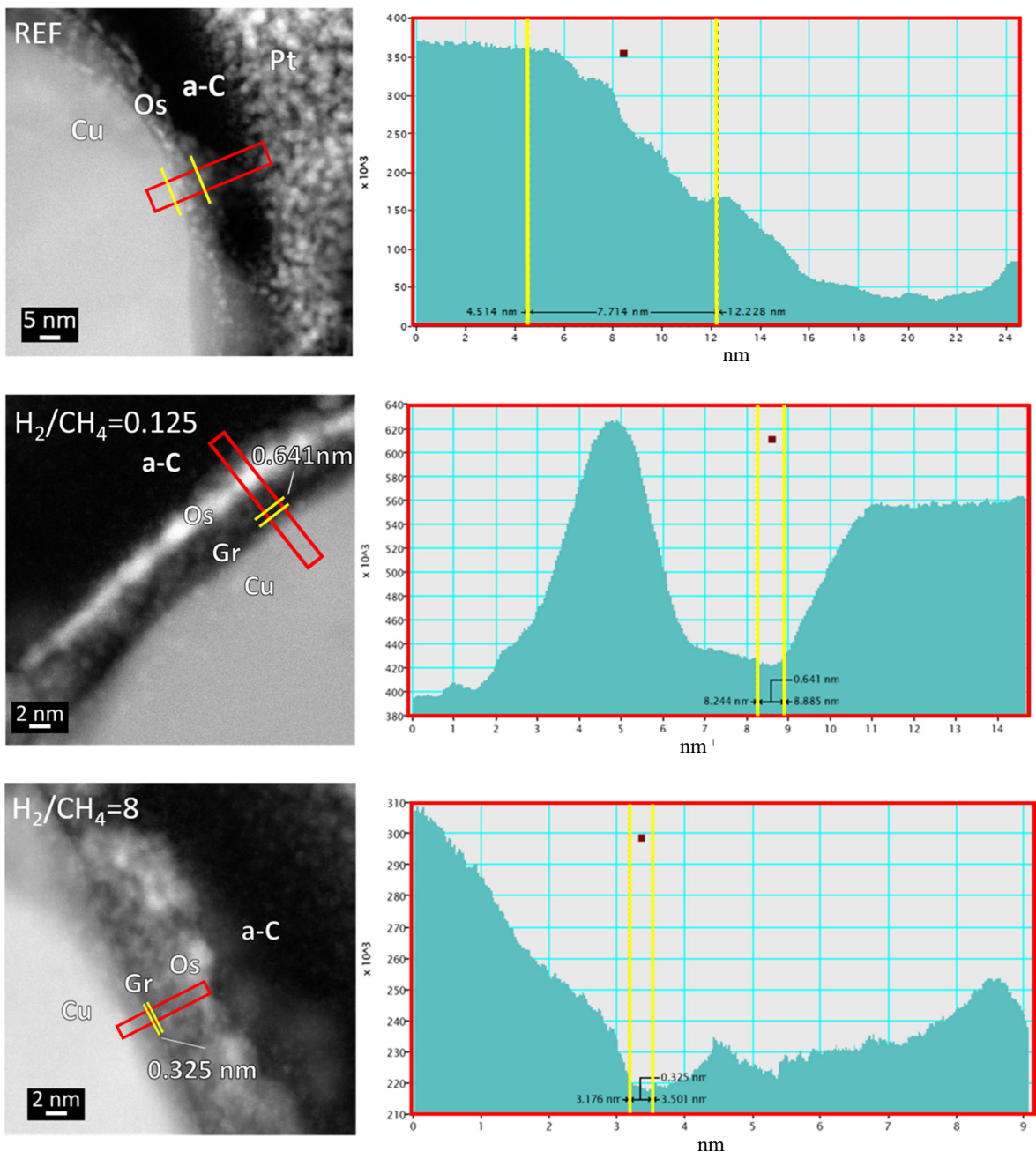


Figure S3: HAADF-STEM image of the Cu ink before and after PECVD of 750mtorr with the corresponding intensity slices.

## Section 2. Derivation of the dependence of electron temperature on total pressure

The equation of motion of electrons under the applied oscillating electric field  $E(t) = E_0 \exp(i\omega t)$  may be written as:

$$m_e \frac{dv_e}{dt} = -eE_0 \exp(i\omega t) - m_e \nu v_e, \quad (1)$$

where  $E_0$ : electric field amplitude,  $\omega$ : the frequency of the applied electric field,  $\nu$ : the collision frequency between electron and the neutral, which is proportional to pressure,  $v_e$ : the velocity of the electron and  $m_e$ : the mass of the electron. Solving for  $v_e$  yields:

$$v_e = -\frac{eE(t)}{m_e(\nu^2 + \omega^2)}(\nu - i\omega) \quad (2)$$

The time-averaged power absorbed by an electron is:

$$\theta_a = \text{Re} \left( \frac{F \cdot v_e^*}{2} \right) = \text{Re} \left( -\frac{eE v_e^*}{2} \right) = \frac{e^2}{2m_e} \frac{\nu}{\nu^2 + \omega^2} E_0^2 \quad (3)$$

And the time-averaged kinetic energy of the electron is:

$$E_k = \frac{1}{2} m_e \text{Re} \left( \frac{v_e v_e^*}{2} \right) = \frac{3}{2} k_b T_e \quad (4)$$

Therefore comparing eq(3) and eq(4) we have:

$$\theta_a = 2\nu E_k \text{ or } T_e = \frac{e^2 E_0^2}{6k_b m_e} \frac{1}{\nu^2 + \omega^2} \quad (5)$$

Under microwave excitation, where  $\frac{\omega}{\nu} \gg 1$  we can approximate eq(5) as:

$$T_e \approx \frac{e^2 E_0^2}{6k_b m_e} \frac{1}{\omega^2} \quad (6)$$

Therefore, the electron temperature is independent of the collision frequency or pressure.

**Reference:** Moisan, M.; Pelletier, J., Hydrodynamic Description of a Plasma. In *Physics of Collisional Plasmas: Introduction to High-Frequency Discharges*, Springer Netherlands: Dordrecht, **2012**, pp 203-335.